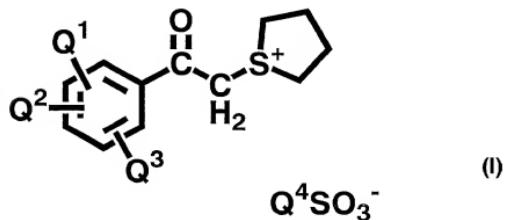


What is claimed is:

1. A chemically amplifying type positive resist composition comprising a resin which has an alkali-soluble group protected by 2-alkyl-2-adamantyl group or 1-adamantyl-1-alkylalkyl group, and which, *per se*, is insoluble or slightly soluble in alkali but becomes soluble in alkali by the action of an acid; and a sulfonium salt acid generating agent represented by the following formula (I):



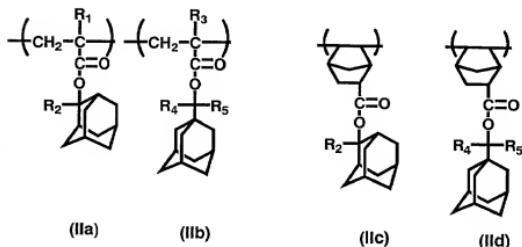
10 where in  $\text{Q}^1$ ,  $\text{Q}^2$  and  $\text{Q}^3$  independently represent hydrogen, hydroxyl, alkyl having 1 to 6 carbon atoms or alkoxy having 1 to 6 carbon atoms; and  $\text{Q}^4$  represents perfluoroalkyl which may have a cyclic structure.

2. The positive resist composition according to claim 1 which contains the resin in an amount of 80 to 99.9 % by weight, and the acid generating agent, including the sulfonium salt acid generating agent represented by the following formula (I) and another acid generating agent, in an amount of 0.1 to 20 % by weight based on the total solid component weight of the resist composition.

3. The positive resist composition according to claim 1

wherein the perfluoroalkylsulfonate anion represented by  $Q^4SO_3^-$  in the formula (I) has 4 or more carbon atoms.

4. The positive resist composition according to claim 1 wherein the resin has at least one polymerization unit selected 5 from those represented by the following formula (IIa), (IIb), (IIc) or (IId):



wherein R<sub>1</sub> and R<sub>3</sub> represent hydrogen or methyl; and R<sub>2</sub>, R<sub>4</sub> and R<sub>5</sub> represent alkyl.

10 5. The positive resist composition according to claim 1 wherein the resin contains a polymerization unit having a group cleavable by the action of an acid within a range of 30 to 80% by mole.

15 6. The positive resist composition according to claim 1 wherein 20% by mole or more of the polymerization unit of the resin is represented by the formulae IIa, IIb, IIc or IId.